AMENDMENTS TO THE CLAIMS

1. **(Currently Amended)** A bipolar electrostatic chuck [[which has]] comprising a first electrode and a second electrode in an interior of an insulating material, said first electrode and second electrode being applied voltages that are different from each other, generates at least an attracting performance by a gradient force, and attracts a sample by allowing a surface of the insulating material to function as a sample attracting plane, characterized in that:

the insulating material comprises ~~is formed by laminating~~ an upper insulating layer, the first electrode, an ~~interelectrode~~ inter-electrode insulating layer, the second electrode, and a lower insulating layer which are laminated in the order of distance from the sample attracting plane ~~in a depth direction of the insulating material~~; and

when ~~the sample attracting plane~~ the insulating material is viewed ~~in a depth direction~~ from a side cross-sectional view, the first electrode has a plurality of gaps, and the second electrode has ~~an area~~ a plurality of areas that ~~is~~ are not overlapped with the first electrode~~, a plurality of first electrodes and a plurality of second electrodes being alternately arranged in a direction in which the area that is not overlapped is crossed a plurality of times~~.

2-3. (Cancelled)

4. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode is formed in a ~~band-like comb teeth~~ comb-like configuration;

the second electrode is formed in a ~~band-like comb teeth~~ comb-like configuration;

~~when the sample attracting plane is viewed in the depth direction, the band-like comb teeth~~ the comb-like configuration of the first and second electrodes are alternately arranged; and

the second electrode is not overlapped with the first electrode in a normal line direction of the sample attracting plane.

5. (Cancelled)

6. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode is formed in a ~~band-like comb teeth~~ comb-like configuration;

the second electrode is formed in a plane having a given planar area; and

a part of the second electrode is overlapped with the first electrode ~~when the sample attracting plane is viewed in the depth direction~~ in a normal line direction of the sample attracting plane.

7. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode is formed in a ~~curb~~ lattice-like configuration;

the second electrode is formed in a plane having a given planar area; and

a part of the second electrode is overlapped with the first electrode ~~when the sample attracting plane is viewed in the depth direction~~ in a normal line direction of the sample attracting plane.

8. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode is formed in a mesh configuration having a plurality of openings each within a given area;

the second electrode is formed in a plane having a given planar area; and

a part of the second electrode is overlapped with the first electrode ~~when the sample attracting plane is viewed in the depth direction~~ in a normal line direction of the sample attracting plane.

9. (Cancelled)

10. (**Currently Amended**) The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode centers on a circular portion having a given circular area, has a plurality of first annular portion that are concentrically disposed at a given interval, and has a first connection portion that connects the circular portion and the first annular portions to each other; and

the second electrode has a plurality of second annular portions having a width smaller than the interval which are concentrically disposed, is formed to have a second connection portion that connects the second annular portions to each other, the first annular portions and the second annular portions being alternately disposed ~~when the sample attracting plane is viewed in the depth direction~~ in a normal line direction of the sample attracting plane.

11. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode centers on a circular portion having a given circular area, has a plurality of first annular portions that are concentrically disposed at a given interval, and has a first connection portion that connects the circular portion and the first annular portions to each other; and

the second electrode has a plurality of second annular portions having a width same as the interval which are concentrically disposed, is formed to have a second connection portion that connects the second annular portions to each other, the first annular portions and the second annular portions being alternately disposed ~~when the sample attracting plane is viewed in the depth direction~~ in a normal line direction of the sample attracting plane.

12. (Cancelled)

13. (Previously Present) The bipolar electrostatic chuck according to claim 1, wherein a distance between the first electrode and the second electrode is equal to or more than 1 μm and equal to or less than 1000 μm.

14. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein:

the first electrode is formed in a ~~band-like comb teeth~~ comb-like configuration; and

in the case where a ~~band-like~~ electrode width ~~z~~ (z) of the first electrode and an ~~interelectrode~~ inter-electrode gap ~~z~~ (z) are made equal to each other, ~~z~~ (z) is in a range of 0.15 to 0.5 mm.

15. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein the ~~interelectrode~~ inter-electrode insulating layer is formed of a resin layer made of one or more resins selected from the group consisting of polyimide, polyamide-imide, polyester, polyethylene terephthalate, epoxy, and acryl.

16. (Previously Presented) The bipolar electrostatic chuck according to claim 1, wherein the resin layer is formed of one or more resin films.

17. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1 wherein the ~~interelectrode~~ inter-electrode insulating layer is formed of a ceramic layer made of one or more elements selected from the group consisting of aluminum oxide, aluminum nitride, silicon carbide, silicon nitride, zirconia, and titania.

18. **(Currently Amended)** The bipolar electrostatic chuck according to claim 1, wherein the ~~interelectrode~~ inter-electrode insulating layer is formed of one or two elements selected from the group consisting of silicon and silicon dioxide.

19. (Previously Presented) The bipolar electrostatic chuck according to claim 1, wherein:

an electrically conductive layer is further formed on the surface of the insulating material; and

the surface of the electrically conductive layer serves as the sample attracting plane.

20. (Previously Presented) The bipolar electrostatic chuck according to claim 1, wherein a sectional configuration of a part or all of the first electrode taken along the depth direction of the sample attracting plane comprises a configuration selected from the group consisting of a rectangle, a square, a circle, and a triangle.

21. (Previously Presented) The bipolar electrostatic chuck according to claim 1, wherein a sectional configuration of a part or all of the second electrode taken along the depth direction of the sample attracting plane comprises a configuration selected from the group consisting of a rectangle, a square, a circle, and a triangle.

22. **(New)** The bipolar electrostatic chuck according to claim 1, wherein the inter-electrode insulating layer has a thickness of 1 to 1000 μm.

23. **(New)** The bipolar electrostatic chuck according to claim 1, wherein the upper insulating layer has a thickness of 10 to 200 μm.

24. **(New)** The bipolar electrostatic chuck according to claim 1, wherein the first electrode is formed in the comb-like configuration, and the inter-electrode gap is in a range of 0.15 to 0.5 mm.

25. **(New)** The bipolar electrostatic chuck according to claim 1, wherein the first electrode is formed in the mesh configuration, and a size of each of the openings is in a range of 0.1 to 3.0 mm.